

09681304_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 09681304 on March 13, 2002

12	438/52	(3 OR, 9 XR)
	Class 438 :	SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
	438/48	MAKING DEVICE OR CIRCUIT RESPONSIVE TO NONELECTRICAL SIGNAL
	438/50	.Physical stress responsive
	438/52	..Having cantilever element
11	310/307	(10 OR, 1 XR)
	Class 310 :	ELECTRICAL GENERATOR OR MOTOR STRUCTURE
	310/300	NON-DYNAMOELECTRIC
	310/306	.Thermal or pyromagnetic
	310/307	..With heat actuated bimetal element
10	438/50	(4 OR, 6 XR)
	Class 438 :	SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
	438/48	MAKING DEVICE OR CIRCUIT RESPONSIVE TO NONELECTRICAL SIGNAL
	438/50	.Physical stress responsive
9	216/2	(4 OR, 5 XR)
	Class 216 :	ETCHING A SUBSTRATE: PROCESSES
	216/2	ETCHING OF SEMICONDUCTOR MATERIAL TO PRODUCE A
N		ARTICLE HAVING A NONELECTRICAL FUNCTION
9	257/417	(2 OR, 7 XR)
	Class 257 :	ACTIVE SOLID-STATE DEVICES
	257/414	RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G., CHEMICAL, STRESS, LIGHT, OR MAGNETIC FIELD
D SENSORS)		
	257/415	.Physical deformation
	257/417	..Strain sensors
7	310/40MM	(3 OR, 4 XR)
	Class 310 :	ELECTRICAL GENERATOR OR MOTOR STRUCTURE
	310/10	DYNAMOELECTRIC
	310/40R	.Rotary
	310/40MM	..Miniature motors
6	257/415	(3 OR, 3 XR)
	Class 257 :	ACTIVE SOLID-STATE DEVICES

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257/414 RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G.,
CHEMICAL, STRESS, LIGHT, OR MAGNETIC FIELD
SENSORS)

257/415 .Physical deformation

6 438/455 (1 OR, 5 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES

5 156/345 (2 OR, 3 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE

156/345 DIFFERENTIAL ETCHING APPARATUS

4 73/514.36 (0 OR, 4 XR)
Class 073 : MEASURING AND TESTING

73/488 SPEED, VELOCITY, OR ACCELERATION

73/514.01 .Acceleration determination utilizing inertial
element

73/514.36 ..Pendulum or beam

4 118/723IR (2 OR, 2 XR)
Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION

118/722 .With treating means (e.g., jarring)

118/723R ..By creating electric field (e.g., gas
activation, plasma, etc.)

118/723I ...Radio frequency antenna or radio frequency
inductive coil discharge means

118/723IRProducing energized gas remotely located
from substrate

4 118/728 (0 OR, 4 XR)
Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION

118/728 .Work support

4 257/254 (1 OR, 3 XR)
Class 257 : ACTIVE SOLID-STATE DEVICES

257/213 FIELD EFFECT DEVICE

257/252 .Responsive to non-optical, non-electrical
signal

257/254 ..Physical deformation (e.g., strain sensor,
acoustic wave detector)

4 310/306 (1 OR, 3 XR)
Class 310 : ELECTRICAL GENERATOR OR MOTOR STRUCTURE

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310/300 NON-DYNAMOELECTRIC

310/306 .Thermal or pyromagnetic

4 438/460 (3 OR, 1 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/460 SEMICONDUCTOR SUBSTRATE DICING

4 438/526 (1 OR, 3 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/510 INTRODUCTION OF CONDUCTIVITY MODIFYING DOPANT
INTO SEMICONDUCTIVE MATERIAL

438/514 .Ion implantation of dopant into semiconductor
region

438/526 ..Forming buried region

4 438/53 (1 OR, 3 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/48 MAKING DEVICE OR CIRCUIT RESPONSIVE TO
NONELECTRICAL SIGNAL

438/50 .Physical stress responsive

438/53 ..Having diaphragm element

3 73/514.21 (2 OR, 1 XR)

Class 073 : MEASURING AND TESTING

73/488 SPEED, VELOCITY, OR ACCELERATION

73/514.01 .Acceleration determination utilizing inertial
element

73/514.16 ..Specific type of electric sensor or specific
type of magnetic sensor

73/514.17 ...Rebalance

73/514.21Pendulum or beam

3 118/723E (2 OR, 1 XR)

Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION

118/722 .With treating means (e.g., jarring)

118/723R ..By creating electric field (e.g., gas
activation, plasma, etc.)

118/723E ...Having glow discharge electrodes (e.g., DC,
AC, RF, etc.)

3 118/723I (0 OR, 3 XR)

Class 118 : COATING APPARATUS

118/715 GAS OR VAPOR DEPOSITION

118/722 .With treating means (e.g., jarring)

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118/723R ..By creating electric field (e.g., gas
activation, plasma, etc.)
118/723I ...Radio frequency antenna or radio frequency
inductive coil discharge means

3 118/723MP (0 OR, 3 XR)

Class 118 : COATING APPARATUS
118/715 GAS OR VAPOR DEPOSITION
118/722 .With treating means (e.g., jarring)
118/723R ..By creating electric field (e.g., gas
activation, plasma, etc.)
118/723MP ...Multiple gas energizing means associated
with one deposition site (i.e., excluding s
ubstrate heater
as an energizing means)

3 118/733 (0 OR, 3 XR)

Class 118 : COATING APPARATUS
118/715 GAS OR VAPOR DEPOSITION
118/733 .Chamber seal

3 148/33.2 (3 OR, 0 XR)

Class 148 : METAL TREATMENT
148/33 BARRIER LAYER STOCK MATERIAL, P-N TYPE
148/33.2 .With recess, void, dislocation, grain
boundaries or channel openings

3 156/247 (0 OR, 3 XR)

Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/60 .Surface bonding and/or assembly therefor
156/247 ..With stripping of adhered lamina

3 156/267 (0 OR, 3 XR)

Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/60 .Surface bonding and/or assembly therefor
156/250 ..With cutting, punching, tearing or severing
156/267 ...Flash, trim or excess removal

3 200/181 (2 OR, 1 XR)

Class 200 : ELECTRICITY: CIRCUIT MAKERS AND BREAKERS
200/181 ELECTROSTRICTIVE OR ELECTROSTATIC

3 204/298.15 (1 OR, 2 XR)

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Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/193 APPARATUS
204/298.01 .Coating, forming or etching by sputtering
204/298.02 ..Coating
204/298.15 ...Specified work holder

3 216/67 (0 OR, 3 XR)
Class 216 : ETCHING A SUBSTRATE: PROCESSES
216/58 GAS PHASE ETCHING OF SUBSTRATE
216/63 .Application of energy to the gaseous etchant
        or to the substrate being etched
216/67 ..Using plasma

3 271/194 (2 OR, 1 XR)
Class 271 : SHEET FEEDING OR DELIVERING
271/278 DELIVERING
271/194 .By pneumatic conveyor

3 271/195 (0 OR, 3 XR)
Class 271 : SHEET FEEDING OR DELIVERING
271/278 DELIVERING
271/194 .By pneumatic conveyor
271/195 ..Using pressurized gas

3 310/309 (2 OR, 1 XR)
Class 310 : ELECTRICAL GENERATOR OR MOTOR STRUCTURE
310/300 NON-DYNAMOELECTRIC
310/308 .Charge accumulating
310/309 ..Electrostatic

3 310/DIG 6 (0 OR, 3 XR)
Class 310 : ELECTRICAL GENERATOR OR MOTOR STRUCTURE
310/DIG 6 Printed-circuit motors and components

3 359/224 (1 OR, 2 XR)
Class 359 : OPTICS: SYSTEMS
359/196 DEFLECTION USING A MOVING ELEMENT OR MEDIUM
        (OFFSETTING OR CHANGING AT LEAST A PORTIO
N OF THE BEAM)
359/223 .By moving a reflective element
359/224 ..Reflective element moved by deformable
        support

3 359/230 (0 OR, 3 XR)
Class 359 : OPTICS: SYSTEMS
359/227 LIGHT CONTROL BY OPAQUE ELEMENT OR MEDIUM
        MOVABLE IN OR THROUGH LIGHT PATH
359/230 .Electro-mechanical

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3 359/290 (0 OR, 3 XR)
 Class 359 : OPTICS: SYSTEMS
 359/237 OPTICAL MODULATOR
 359/238 .Light wave temporal modulation (e.g.,
 frequency, amplitude, etc.)
 359/290 ..By changing physical characteristics (e.g.,
 shape, size or contours) of an optical elem
 ent

3 359/291 (2 OR, 1 XR)
 Class 359 : OPTICS: SYSTEMS
 359/237 OPTICAL MODULATOR
 359/238 .Light wave temporal modulation (e.g.,
 frequency, amplitude, etc.)
 359/290 ..By changing physical characteristics (e.g.,
 shape, size or contours) of an optical ele
 ment

359/291 ...Shape or contour of light control surface
 altered

3 430/22 (2 OR, 1 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/22 REGISTRATION OR LAYOUT PROCESS OTHER THAN COLO
 R

PROOFING

3 438/458 (2 OR, 1 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES
 438/458 .Subsequent separation into plural bodies
 (e.g., delaminating, dicing, etc.)

3 438/459 (0 OR, 3 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES
 438/459 .Thinning of semiconductor substrate

3 438/48 (0 OR, 3 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 438/48 MAKING DEVICE OR CIRCUIT RESPONSIVE TO
 NONELECTRICAL SIGNAL

3 438/515 (3 OR, 0 XR)

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Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/510 INTRODUCTION OF CONDUCTIVITY MODIFYING DOPANT
INTO SEMICONDUCTIVE MATERIAL

438/514 .Ion implantation of dopant into semiconductor
region

438/515 ..Ionized molecules

3 438/706 (0 OR, 3 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)

3 438/712 (0 OR, 3 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)

438/707 ..Utilizing electromagnetic or wave energy

438/710 ...By creating electric field (e.g., plasma,
glow discharge, etc.)

438/712Reactive ion beam etching (i.e., RIBE)

3 438/739 (0 OR, 3 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING

438/706 .Vapor phase etching (i.e., dry etching)

438/735 ..Differential etching of semiconductor
substrate

438/737 ...Substrate possessing multiple layers

438/738Selectively etching substrate possessing
multiple layers of differing etch characte

istics

438/739Lateral etching of intermediate layer
(i.e., undercutting)

3 445/24 (1 OR, 2 XR)
Class 445 : ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR
DEVICE MANUFACTURING

445/1 PROCESS

445/23 .With assembly or disassembly

445/24 ..Display or gas panel making

2 29/596 (0 OR, 2 XR)
Class 029 : METAL WORKING

29/592 METHOD OF MECHANICAL MANUFACTURE

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29/592.1 .Electrical device making
29/596 ..Dynamoelectric machine

2 29/598 (1 OR, 1 XR)
Class 029 : METAL WORKING
29/592 METHOD OF MECHANICAL MANUFACTURE
29/592.1 .Electrical device making
29/596 ..Dynamoelectric machine
29/598 ...Rotor

2 73/514.16 (2 OR, 0 XR)
Class 073 : MEASURING AND TESTING
73/488 SPEED, VELOCITY, OR ACCELERATION
73/514.01 .Acceleration determination utilizing inertial
element
73/514.16 ..Specific type of electric sensor or specific
type of magnetic sensor

2 73/514.32 (0 OR, 2 XR)
Class 073 : MEASURING AND TESTING
73/488 SPEED, VELOCITY, OR ACCELERATION
73/514.01 .Acceleration determination utilizing inertial
element
73/514.16 ..Specific type of electric sensor or specific
type of magnetic sensor
73/514.32 ...Capacitive sensor

2 73/654 (0 OR, 2 XR)
Class 073 : MEASURING AND TESTING
73/570 VIBRATION
73/649 .Sensing apparatus
73/652 ..With inertia element
73/654 ...With electrically controlled indicator

2 156/230 (0 OR, 2 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/60 .Surface bonding and/or assembly therefor
156/230 ..Direct contact transfer of adhered lamina
from carrier to base

2 156/233 (0 OR, 2 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/60 .Surface bonding and/or assembly therefor
156/230 ..Direct contact transfer of adhered lamina

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from carrier to base

156/233 ...Metal foil lamina

2 156/241 (2 OR, 0 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/60 .Surface bonding and/or assembly therefor
156/230 ..Direct contact transfer of adhered lamina
from carrier to base
156/241 ...To base coated with adhesive

2 156/250 (0 OR, 2 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/60 .Surface bonding and/or assembly therefor
156/250 ..With cutting, punching, tearing or severing

2 156/256 (0 OR, 2 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/60 .Surface bonding and/or assembly therefor
156/250 ..With cutting, punching, tearing or severing
156/256 ...Prior to assembly

2 156/344 (1 OR, 1 XR)
Class 156 : ADHESIVE BONDING AND MISCELLANEOUS CHEMICAL
MANUFACTURE
156/1 METHODS
156/344 .Delaminating, per se

2 204/192.32 (0 OR, 2 XR)
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/192.1 .Coating, forming or etching by sputtering
204/192.32 ..Sputter etching

2 204/192.37 (2 OR, 0 XR)
Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
204/192.1 .Coating, forming or etching by sputtering
204/192.32 ..Sputter etching
204/192.35 ...Etching specified material
204/192.37Silicon containing

2 204/298.32 (0 OR, 2 XR)

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Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
 204/193 APPARATUS
 204/298.01 .Coating, forming or etching by sputtering
 204/298.31 ..Etching
 204/298.32 ...Measuring, analyzing or testing

2 204/298.36 (0 OR, 2 XR)

Class 204 : CHEMISTRY: ELECTRICAL AND WAVE ENERGY
 204/193 APPARATUS
 204/298.01 .Coating, forming or etching by sputtering
 204/298.31 ..Etching
 204/298.36 ...Beam or directed flux etching (e.g., ion beam, etc.)

2 216/52 (0 OR, 2 XR)

Class 216 : ETCHING A SUBSTRATE: PROCESSES
 216/52 MECHANICALLY SHAPING, DEFORMING, OR ABRADING O

F

SUBSTRATE

2 225/2 (0 OR, 2 XR)

Class 225 : SEVERING BY TEARING OR BREAKING
 225/1 METHODS
 225/2 .With preliminary weakening

2 244/130 (0 OR, 2 XR)

Class 244 : AERONAUTICS
 244/117R AIRCRAFT STRUCTURE
 244/129.1 .Details
 244/130 ..Aerodynamic resistance reducing

2 244/204 (2 OR, 0 XR)

Class 244 : AERONAUTICS
 244/34R AIRCRAFT SUSTENTATION
 244/35R .Sustaining airfoils
 244/198 ..With lift modification
 244/201 ...Variable
 244/204By controlling boundary layer

2 250/492.21 (0 OR, 2 XR)

Class 250 : RADIANT ENERGY
 250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
 250/492.2 .Irradiation of semiconductor devices
 250/492.21 ..Ion bombardment

2 257/418 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES
 257/414 RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G.,

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CHEMICAL, STRESS, LIGHT, OR MAGNETIC FIE

LD SENSORS)

257/415 .Physical deformation
 257/417 ..Strain sensors
 257/418 ...With means to concentrate stress

2 257/419 (1 OR, 1 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES
 257/414 RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G.,
 CHEMICAL, STRESS, LIGHT, OR MAGNETIC FI

ELD SENSORS)

257/415 .Physical deformation
 257/417 ..Strain sensors
 257/418 ...With means to concentrate stress
 257/419With thinned central active portion of
 semiconductor surrounded by thick insensiti

ve portion

(e.g., diaphragm type strain gauge)

2 257/420 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES
 257/414 RESPONSIVE TO NON-ELECTRICAL SIGNAL (E.G.,
 CHEMICAL, STRESS, LIGHT, OR MAGNETIC FIEL

D SENSORS)

257/415 .Physical deformation
 257/420 ..Means to reduce sensitivity to physical
 deformation

2 257/659 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES
 257/659 WITH SHIELDING (E.G., ELECTRICAL OR MAGNETIC
 SHIELDING, OR FROM ELECTROMAGNETIC RADIATIO

N OR CHARGE

PARTICLES)

2 257/737 (0 OR, 2 XR)

Class 257 : ACTIVE SOLID-STATE DEVICES
 257/734 COMBINED WITH ELECTRICAL CONTACT OR LEAD
 257/737 .Bump leads

2 310/268 (0 OR, 2 XR)

Class 310 : ELECTRICAL GENERATOR OR MOTOR STRUCTURE
 310/10 DYNAMOELECTRIC
 310/40R .Rotary
 310/261 ..Rotor structure
 310/264 ...Armatures
 310/268Disc

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2 315/111.41 (0 OR, 2 XR)
 Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
 SUPPLY TO THE DISCHARGE SPACE

315/111.21 .Plasma generating
 315/111.41 ..With magnetic field

2 315/111.71 (0 OR, 2 XR)
 Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL
 SUPPLY TO THE DISCHARGE SPACE

315/111.21 .Plasma generating
 315/111.41 ..With magnetic field
 315/111.71 ...Plasma containment

2 359/198 (1 OR, 1 XR)
 Class 359 : OPTICS: SYSTEMS

359/196 DEFLECTION USING A MOVING ELEMENT OR MEDIUM
 (OFFSETTING OR CHANGING AT LEAST A PORTIO
 N OF THE BEAM)

359/197 .Using a periodically moving element (periodic
 change of optically reflecting, refracting
 or diffracting
 element)

359/198 ..Particular mount or driver for element

2 359/223 (0 OR, 2 XR)
 Class 359 : OPTICS: SYSTEMS

359/196 DEFLECTION USING A MOVING ELEMENT OR MEDIUM
 (OFFSETTING OR CHANGING AT LEAST A PORTION
 OF THE BEAM)

359/223 .By moving a reflective element

2 361/233 (1 OR, 1 XR)
 Class 361 : ELECTRICITY: ELECTRICAL SYSTEMS AND DEVICES

361/230 ELECTRIC CHARGE GENERATING OR CONDUCTING MEANS
 (E.G., CHARGING OF GASES)

361/233 .Use of forces of electric charge or field

2 427/523 (0 OR, 2 XR)
 Class 427 : COATING PROCESSES

427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
 WAVE, OR PARTICULATE ENERGY

427/523 .Ion plating or implantation

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2 427/524 (0 OR, 2 XR)
 Class 427 : COATING PROCESSES
 427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
 WAVE, OR PARTICULATE ENERGY
 427/523 .Ion plating or implantation
 427/524 ..With simultaneous sputter etching of
 substrate

2 427/527 (0 OR, 2 XR)
 Class 427 : COATING PROCESSES
 427/457 DIRECT APPLICATION OF ELECTRICAL, MAGNETIC,
 WAVE, OR PARTICULATE ENERGY
 427/523 .Ion plating or implantation
 427/527 ..Silicon present in substrate, plating, or
 implanted layer

2 430/319 (0 OR, 2 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF
 RADIATION SENSITIVE MATERIAL, OR PRODUCIN

G NONPLANAR OR
 PRINTING SURFACE - PROCESS, COMPOSITION,
 OR PRODUCT

430/311 .Making electrical device
 430/319 ..Named electrical device

2 430/5 (1 OR, 1 XR)
 Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS,
 COMPOSITION, OR PRODUCT THEREOF
 430/4 RADIATION MODIFYING PRODUCT OR PROCESS OF
 MAKING
 430/5 .Radiation mask

2 438/107 (1 OR, 1 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 438/106 PACKAGING (E.G., WITH MOUNTING, ENCAPSULATING,
 ETC.) OR TREATMENT OF PACKAGED SEMICONDUCT

OR
 438/107 .Assembly of plural semiconductive substrates
 each possessing electrical device

2 438/120 (2 OR, 0 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS
 438/106 PACKAGING (E.G., WITH MOUNTING, ENCAPSULATING,
 ETC.) OR TREATMENT OF PACKAGED SEMICONDUCT

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OR

438/120 .With vibration step

2 438/127 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/106 PACKAGING (E.G., WITH MOUNTING, ENCAPSULATING,
ETC.) OR TREATMENT OF PACKAGED SEMICONDUCT

OR

438/127 .Encapsulating

2 438/26 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/22 MAKING DEVICE OR CIRCUIT EMISSIVE OF
NONELECTRICAL SIGNAL

438/26 .Packaging (e.g., with mounting, encapsulating

,

etc.) or treatment of packaged semiconducto

r

2 438/28 (2 OR, 0 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/22 MAKING DEVICE OR CIRCUIT EMISSIVE OF
NONELECTRICAL SIGNAL

438/26 .Packaging (e.g., with mounting, encapsulating

,

etc.) or treatment of packaged semiconduct

or

438/28 ..Plural emissive devices

2 438/34 (0 OR, 2 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/22 MAKING DEVICE OR CIRCUIT EMISSIVE OF
NONELECTRICAL SIGNAL

438/34 .Making emissive array

2 438/406 (1 OR, 1 XR)

Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/400 FORMATION OF ELECTRICALLY ISOLATED LATERAL
SEMICONDUCTIVE STRUCTURE

438/404 .Total dielectric isolation

438/406 ..Bonding of plural semiconductive substrates

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2 438/456 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES
438/456 .Having enclosed cavity

2 438/457 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/455 BONDING OF PLURAL SEMICONDUCTOR SUBSTRATES
438/457 .Warping of semiconductor substrate

2 438/464 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/460 SEMICONDUCTOR SUBSTRATE DICING
438/464 .With attachment to temporary support or
carrier

2 438/51 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/48 MAKING DEVICE OR CIRCUIT RESPONSIVE TO
NONELECTRICAL SIGNAL
438/50 .Physical stress responsive
438/51 ..Packaging (e.g., with mounting,
encapsulating, etc.) or treatment of packa
ged
semiconductor

2 438/692 (0 OR, 2 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING
438/690 .Combined with the removal of material by
nonchemical means (e.g., ablating, abradi
ng, etc.)
438/691 ..Combined mechanical and chemical material
removal
438/692 ...Simultaneous (e.g., chemical-mechanical
polishing, etc.)

2 438/745 (1 OR, 1 XR)
Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING
438/745 .Liquid phase etching

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2 438/753 (0 OR, 2 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/689 CHEMICAL ETCHING
 438/745 .Liquid phase etching
 438/753 ..Silicon

2 438/800 (0 OR, 2 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/800 MISCELLANEOUS

2 438/933 (0 OR, 2 XR)
 Class 438 : SEMICONDUCTOR DEVICE MANUFACTURING: PROCESS

438/933 GERMANIUM OR SILICON OR GE-SI ON III-V

2 445/50 (0 OR, 2 XR)
 Class 445 : ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR
 DEVICE MANUFACTURING

445/1 PROCESS
 445/46 .Electrode making
 445/49 ..Electrode shaping
 445/50 ...Emissive type

2 451/388 (1 OR, 1 XR)
 Class 451 : ABRADING

451/364 WORK HOLDER
 451/388 .Vacuum

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Most Frequently Occurring Classifications of Patents Returned
From A Search of 09681304 on March 13, 2002

Original Classifications

10	310/307
4	216/2
4	438/50
3	148/33.2
3	257/415
3	310/40MM
3	438/460
3	438/515
3	438/52
2	73/514.16
2	73/514.21
2	118/723E
2	118/723IR
2	156/241
2	156/345
2	200/181
2	204/192.37
2	244/204
2	257/417
2	271/194
2	310/309
2	359/291
2	430/22
2	438/120
2	438/28
2	438/458

Cross-Reference Classifications

9	438/52
7	257/417
6	438/50
5	216/2
5	438/455
4	73/514.36
4	118/728
4	310/40MM
3	118/723I
3	118/723MP
3	118/733
3	156/247
3	156/267
3	156/345
3	216/67

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3 257/254
3 257/415
3 271/195
3 310/306
3 310/DIG 6
3 359/230
3 359/290
3 438/459
3 438/48
3 438/526
3 438/53
3 438/706
3 438/712
3 438/739
2 29/596
2 73/514.32
2 73/654
2 118/723IR
2 156/230
2 156/233
2 156/250
2 156/256
2 204/192.32
2 204/298.15
2 204/298.32
2 204/298.36
2 216/52
2 225/2
2 244/130
2 250/492.21
2 257/418
2 257/420
2 257/659
2 257/737
2 310/268
2 315/111.41
2 315/111.71
2 359/223
2 359/224
2 427/523
2 427/524
2 427/527
2 430/319
2 438/127
2 438/26
2 438/34
2 438/456
2 438/457

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2 438/464
2 438/51
2 438/692
2 438/753
2 438/800
2 438/933
2 445/24
2 445/50

Combined Classifications

12 438/52
11 310/307
10 438/50
9 216/2
9 257/417
7 310/40MM
6 257/415
6 438/455
5 156/345
4 73/514.36
4 118/723IR
4 118/728
4 257/254
4 310/306
4 438/460
4 438/526
4 438/53
3 73/514.21
3 118/723E
3 118/723I
3 118/723MP
3 118/733
3 148/33.2
3 156/247
3 156/267
3 200/181
3 204/298.15
3 216/67
3 271/194
3 271/195
3 310/309
3 310/DIG 6
3 359/224
3 359/230
3 359/290
3 359/291
3 430/22
3 438/458

09681304_CLS

3 438/459
3 438/48
3 438/515
3 438/706
3 438/712
3 438/739
3 445/24
2 29/596
2 29/598
2 73/514.16
2 73/514.32
2 73/654
2 156/230
2 156/233
2 156/241
2 156/250
2 156/256
2 156/344
2 204/192.32
2 204/192.37
2 204/298.32
2 204/298.36
2 216/52
2 225/2
2 244/130
2 244/204
2 250/492.21
2 257/418
2 257/419
2 257/420
2 257/659
2 257/737
2 310/268
2 315/111.41
2 315/111.71
2 359/198
2 359/223
2 361/233
2 427/523
2 427/524
2 427/527
2 430/319
2 430/5
2 438/107
2 438/120
2 438/127
2 438/26
2 438/28

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2 438/34
2 438/406
2 438/456
2 438/457
2 438/464
2 438/51
2 438/692
2 438/745
2 438/753
2 438/800
2 438/933
2 445/50
2 451/388

09681304_QUAL

6335224 95
6287765 86
6124663 84
5389182 81
5905007 80
6071819 80
5923995 76
6188814 76
5647044 76
5710065 73
5979728 73
6116756 72
6180428 72
5637539 71
5912094 71
5955817 71
5994816 71
6023121 71
6078103 71
6096149 71
6114794 71
6173650 71
6180536 71
6239473 71
6310018 71
6321654 71
6342430 71
5955659 70
6142358 70
5761350 70
6008776 70
6045712 70
6072686 70
6225145 70
6225145 70
5445559 69
5605489 69
5938952 69
6140144 69
6303986 69
5910856 69
5914553 69
6057520 69
6127812 69
6211598 69
6211598 69
6229683 69
6236491 69

09681304_QUAL

5837935 68
5929497 68
6060336 68
6109222 68
6140646 68
6210988 65
6210988 65
5412265 65
5592037 65
5685062 65
6054335 65
6167809 65
5331236 65
5378330 65
5426070 65
5628917 65
5642015 65
5645684 65
5660680 65
5717631 65
5726480 65
5755408 65
5783340 65
5786621 65
5804084 65
5843832 65
5874675 65
5903099 65
5907768 65
5909078 65
5914507 65
5917226 65
5919364 65
5941481 65
5962949 65
5976994 65
5985742 65
5990473 65
5994207 65
5994638 65
6000280 65
6010579 65
6013567 65
6013563 65
6015599 65
6025767 65
6027112 65
6028343 65

09681304_QUAL

6033974 65
6039316 65
6040935 65
6048411 65
6051073 65
6058778 65
6058778 65
6065864 65
6113735 65
6114188 65
6119052 65
6116863 65
6120660 65
6123985 65
6134042 65
6137206 65
6136243 65
6143583 65
6143997 65
6146979 65
6146227 65
6149190 65
6153524 65
6155490 65
6155909 65
6156652 65
6159824 65
6159825 65
6162705 65
6166478 65
6169321 65
6170332 65
6171879 65
6171965 65
6184111 65
6186091 65
6187110 65
6193501 65
6199575 65
6199874 65
6204151 65
6207005 65
6210514 65
6213050 65
6217724 65
6218205 65
6218209 65
6218762 65

09681304_QUAL

6220096 65
6210514 65
6213050 65
6217724 65
6218205 65
6218209 65